Form PTO 1449		U.S. DEPARTMENT	OF COMMERCE	ATTY DOCKET NO.		SERIAL NO.				
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				APPLICANT						
LIST OF	REFE	RENCES CITED BY API	PLICANT	Yoshiaki SAITO, et al.						
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Examiner HIEN NGUTEN						Date Considered 6/25/04				
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.										